





Effects of hydrogen on device total ionizing dose and dose rate response

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Topics



Effect of hydrogen on dose rate sensitivity

- ELDRS mechanism and modeling
- Results of TID exposure at different dose rates in H environment
- Modeling the effect of H on ELDRS

Effects of hydrogen on TID and annealing response (Covered in Appendix)

- Previous TID experiment in hydrogen
- Un-biased annealing in air/hydrogen



ELDRS in bipolar devices



 Enhanced Low Dose Rate Sensitivity in bipolar devices



After Witczak et al, IEEE Trans. Nucl. Sci., 1998



Existing ELDRS Models







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Some Key ELDRS Processes



ELDRS really is: Reduced High Dose Rate Sensitivity



High space charge induced localized E-field @ HDR

- Increases recombination of n⁻/p⁺
- Increases probability of n⁻ trapping, recombining with free holes



 Increases probability of trapped p⁺ annihilation by n⁻



Modeling ELDRS



ELDRS mechanism simulation

- Using 2D
 COMSOL FES
 @ASU
- Reduced hole yield at HDR due to increased n⁻/p⁺ recombination caused by space charge
- Hole yield directly affects H⁺ and N_{it} generation





Modeling ELDRS



- Hole flux is affected by applied E-field
- Appied E-field directly affects ELDRS response





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Effect of H₂ on ELDRS



ELDRS/H₂ Experiment on bipolar parts

 Gated bipolar test structures (GLPNP) with P-glass passivation (ASU).



Presenting at NSREC 2008



Effect of H₂ on ELDRS



ELDRS/H₂ Experiment on bipolar parts (LM193)



Presenting at NSREC 2008



Effect of H₂ on radiation response





- GLPNPs exposed to 30krad
 Co-60 gamma rays at 20rad/s
- Enhanced buildup in N_{it} as H2 concentration increases due to H₂ cracking reactions

 $H_2 + 2D \rightarrow 2DH$

After Chen et al, IEEE Trans. Nucl. Sci., 2007



Impact of hydrogen on ELDRS



ELDRS response also changes with H₂



Modeling ELDRS with Hydrogen



Comsol 2D ELDRS simulation with 4 different H concentrations





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Ongoing experiments



- ELDRS Experiment is planned for April and May, 08
 - All test devices are P-glass passivated devices showing ELDRS
 - Devices will have either air and 100% H₂ in radiation environment
 - Data points will be taken at 0.1 rad/s, 150 rad/s, and 20 rad/s







- Effect of hydrogen on ELDRS
 - Hole yield is dependent on dose rate
 - High hydrogen concentration in low-field oxide shifts the ELDRS response of bipolar devices.
 - Preliminary simulations shows good qualitative response.
- Annealing experiments after TID exposure in H₂
 - No signification annealing of N_{it}.
 - Large differences in N_{ot} annealing slopes.
 - Differences in annealing slope maybe due to spatial distribution of H-induced trapped charge (p⁺ or H⁺).





- Isochronal annealing and study the effect of Efield and spatial distribution of H-induced trapped charge.
- REOS (Sandia) and COMSOL(ASU) modeling of ELDRS and TID response.
- FTIR and ERD (Elastic Recoil Detection) measurements on H-defect properties in samples irradiated in H_{2.}



Appendix



Effects of hydrogen on TID and annealing response

- Previous TID experiment in hydrogen
- Un-biased annealing in air/hydrogen
- Biased annealing in air



Enhanced TID degradation in H₂





- BJTs exposed to 30krad Co-60 gamma rays
- Enhanced buildup in N_{it}
- Enhanced buildup in N_{ot}

After Chen et al, IEEE Trans. Nucl. Sci., 2007



Annealing in air





- Anneal with no bias
- N_{ot} anneal slope greater for higher H₂
- Annealing experiments on N_{it} showed little change at room temperature

Annealing in 100% H₂





- Anneal with no bias
- Sudden drop of N_{ot} corresponds w/ increase of N_{it}

• *
$$H_2 + D^+ \rightarrow DH + H^+$$

* After Mrstik & Rendell, IEEE Trans. Nucl. Sci., 1991

Brief Summary of Results







Mechanism of N_{ot} Annealing





$$\frac{\partial \rho_{ot}(x,t)}{\partial t} = -g(x,t)\rho_{ot}(x,t)$$

$$\rho_{ot}(x,t) = \rho_{ot,0}(x)e^{-\alpha t e^{-\beta x}}$$

*If assuming uniform spatial distribution near the Si/SiO*₂ *interface and low E-fields in the oxide:*

$$\Delta N_{ot}(t) \approx \frac{-q\rho_{ot,0}}{\beta} \ln(\alpha t)$$



Biased annealing results



Biased annealing behavior of rad-induced N_{ot}



- With applied bias, change in annealing rate.
- Usually the tunneling equation is solved numerically with a E-field dependent tunneling probability:

$$g(x,t) = \alpha(E) \exp(-Z(E))$$

After Mclean, TNS, 1976